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APPLICATION NO.	FILIN	IG DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/782,741	02/	19/2004	Patrick J. Sercel	JPSA 001	1664
32047	7590	10/18/2005		EXAMINER	
	N, TUCKE	ELVE, MARIA	ELVE, MARIA ALEXANDRA		
	55 SOUTH COMMERICAL STREET MANCHESTER, NH 03101			ART UNIT	PAPER NUMBER
	•			1725	

DATE MAILED: 10/18/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/782,741	SERCEL ET AL.				
Office Action Summary	Examiner	Art Unit				
	M. Alexandra Elve	1725				
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet with the	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REI WHICHEVER IS LONGER, FROM THE MAILING - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory perions for reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the may be arrived patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION 1.136(a). In no event, however, may a reply be liod will apply and will expire SIX (6) MONTHS fro tute, cause the application to become ABANDON	ON. timely filed om the mailing date of this communication. NED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 30) August 2005.					
2a) ☐ This action is FINAL . 2b) ☑ T	his action is non-final.					
3) Since this application is in condition for allow	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice unde	er Ex parte Quayle, 1935 C.D. 11,	453 O.G. 213.				
Disposition of Claims						
4) ☑ Claim(s) 1-40 is/are pending in the applicating 4a) Of the above claim(s) 22-40 is/are withdress. 5) ☐ Claim(s) is/are allowed. 6) ☑ Claim(s) 1-14 and 16-20 is/are rejected. 7) ☑ Claim(s) 15 and 21 is/are objected to. 8) ☐ Claim(s) are subject to restriction and	rawn from consideration.					
Application Papers						
9) ☐ The specification is objected to by the Exam 10) ☑ The drawing(s) filed on 19 February 2004 is the second Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) ☐ The oath or declaration is objected to by the	fare: a) \square accepted or b) \boxtimes object the drawing(s) be held in abeyance. Section is required if the drawing(s) is constant.	ee 37 CFR 1.85(a). bjected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119	•					
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the papplication from the International Bure * See the attached detailed Office action for a line in the internation of the internati	ents have been received. ents have been received in Applica riority documents have been receiveau (PCT Rule 17.2(a)).	ntion No ved in this National Stage				
Attachment(s)	_					
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/Paper No(s)/Mail Date <u>8/16/05, 8/26/04</u>. 	4) Interview Summar Paper No(s)/Mail (08) 5) Notice of Informal 6) Other:					

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DETAILED ACTION

Election/Restrictions

Applicant's election with traverse of group I in the reply filed on 8/30/05 is acknowledged. The traversal is on the ground(s) that inventions are related. This is not found persuasive because a method for forming a variable astigmatic focal beam spot, a method of separating a wafer, an apparatus for delivering a laser beam, a method for scribing a semiconductor wafer, and a method for scribing a sapphire substrate are not the same inventions and in fact are different inventions.

The requirement is still deemed proper and is therefore made FINAL.

Claims 22-40 are withdrawn from further consideration pursuant to 37 CFR 1.142(b), as being drawn to nonelected groups, there being no allowable generic or linking claim. Applicant timely traversed the restriction (election) requirement in the reply filed on 8/30/05.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1, 5, 7-10, 13 & 16-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over MacAnally et al. (USPN 4,752,922) in view of Yamanaka (USPN 6,266,302).

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MacAnally et al. discloses a laser system having an astigmatic focusing system, collimation and expansion of the beam(s), the use of a collimator telescope, lens and the formation of multiple focal points.

MacAnally et al. does not specifically teach convergence.

Yamanaka discloses an optical device, which uses an astigmatic element placed in a convergent optical system for focusing the beam and emitting an astigmatic beam.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use convergence as taught by Yamanaka in the MacAnally et al. process because it fully tailors the beam and hence optimizes the cutting area.

Claims 2-4, 11-12 & 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over MacAnally et al. and Yamanaka, as stated in the above paragraph and further in view of Liu et al. (USPN 6,580,054).

MacAnally et al. and Yamanaka do not teach a solid-state laser, UV, pulse durations or the processing of a sapphire substrate.

Liu et al. discloses a process for scribing sapphire substrates using a śolid-state laser, which emits UV pulses. GaN is manufactured on the sapphire surface. Laser pulses of 10 to 30 nanoseconds, with a spot size of 5 to 25 microns are used to process the substrate. Grooves of about 40 microns are cut into the substrate and debris is removed using an exhaust system.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use sapphire, a solid state UV laser and noted the pulse durations, as

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taught by Liu et al. in the MacAnally et al. and Yamanaka process because these are merely variations of laser types and the recording of data and parameters, in order to characterize the process operation.

Claim 6 is rejected under 35 U.S.C. 103(a) as being unpatentable over MacAnally et al. and Yamanaka, as stated in the above paragraph and further in view of Snyder (USPN 5,181,224).

MacAnally et al. and Yamanaka do not teach the type of lens in the system.

Snyder discloses a laser system, which works with astigmatism features in laser processing. Plano convex and convex-concave devices are used to collimate the laser beam.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use plano convex and concave devices, as taught by Snyder in the MacAnally et al. and Yamanaka processing because these are merely apparatus variants.

Allowable Subject Matter

Claims 15 & 21 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The following is a statement of reasons for the indication of allowable subject matter: the prior art does not teach a metal film of Mo or Cu and use of a surfactant.

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Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. See US PTO-890.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to M. Alexandra Elve whose telephone number is 571-272-1173. The examiner can normally be reached on 6:30-3:00 Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Dunn can be reached on 571-272-1171. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

October 16, 2005.

M. Alexandra Elve Primary Examiner 1725